



# 제 29회 한국반도체학술대회

The 29th Korean Conference on Semiconductors

2022년 1월 24일(월)~ 26일(수) | 강원도 하이원 그랜드호텔(컨벤션타워)

2022년 1월 25일(화), 16:00-17:45

Room J (하트 III, 6층)

## B. Patterning 분과

### [TJ3-B] Advanced Etch Processes

좌장: 채희엽 교수(성균관대학교)

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| <p>TJ3-B-1<br/>16:00-16:30</p> | <p><b>Etch Characteristics of SiO<sub>2</sub> Using Fluorinated Ether Plasmas</b><br/>Sanghuyn You and Chang-Koo Kim<br/><i>Ajou University</i></p>  |
| <p>TJ3-B-2<br/>16:30-16:45</p> | <p><b>Influence of Organic Additives to Ethylenediamine on Etch Characteristics of Copper Thin Films Using High Density Plasma</b><br/>Eun Taek Lim, Sung Yong Park, Ji Soo Lee, Seung Hyun Kim, Hyun Mok Jeong, and Chee Won Chung<br/><i>Department of Chemical Engineering, Inha University</i></p>   |
| <p>TJ3-B-3<br/>16:45-17:00</p> | <p><b>Isotropic Atomic Layer Etching of Al<sub>2</sub>O<sub>3</sub> Using NF<sub>3</sub> Remote Plasma and Al Precursors</b><br/>Yewon Kim<sup>1</sup>, Okhyeon Kim<sup>1</sup>, Khabib Khumaini<sup>1,2</sup>, and Won-Jun Lee<sup>1</sup><br/><sup>1</sup><i>Department of Nanotechnology and Advanced Materials Engineering, Sejong University, </i><sup>2</sup><i>Department of Chemistry, Univeritas Pertamina</i></p>  |
| <p>TJ3-B-4<br/>17:00-17:15</p> | <p><b>Low-Temperature Plasma Atomic Layer Etching of Molybdenum via Sequential Oxidation and Chlorination</b><br/>Yebin Lee<sup>1</sup>, Yongjae Kim<sup>2</sup>, Hyeongwu Lee<sup>2</sup>, Jiwon Son<sup>3</sup>, and Heeyeop Chae<sup>1,2</sup><br/><sup>1</sup><i>School of Chemical Engineering, Sungkyunkwan University, </i><sup>2</sup><i>SKKU Advanced Institute of Nanotechnology (SAINT), Sungkyunkwan University, </i><sup>3</sup><i>Mechatronics R&amp;D Center, Samsung Electronics Co., Ltd.</i></p>                   |
| <p>TJ3-B-5<br/>17:15-17:30</p> | <p><b>Ar/C<sub>4</sub>F<sub>6</sub> 혼합 가스와 ICP-RF bias system 에서의 플라즈마 특성 분석을 통한 원자층 식각에 대한 연구</b><br/>Min Young Yoon<sup>1,2</sup>, Hee Jung Yeom<sup>1</sup>, Jung Hyung Kim<sup>1</sup>, Won Chegal<sup>1</sup>, Yong Jai Cho<sup>1</sup>, Deuk-Chul Kwon<sup>3</sup>, Jong-Ryul Jeong<sup>2</sup>, and Hyo-Chang Lee<sup>1</sup><br/><sup>1</sup><i>KRISS, </i><sup>2</sup><i>Department of Materials Science &amp; Engineering, Chungnam National University, </i><sup>3</sup><i>Korea Institute of Fusion Energy (KFE)</i></p> |
| <p>TJ3-B-6<br/>17:30-17:45</p> | <p><b>Photolithographically Defined Copolymeric Surfaces Enabling Perovskite Pattern Formation</b><br/>Sol An<sup>1</sup>, Geemin Kim<sup>1</sup>, Seok Ki Hyeong<sup>2</sup>, Seoung Ki Lee<sup>2</sup> and Naechul Shin<sup>1</sup>, and Myungwoong Kim<sup>1</sup><br/><sup>1</sup><i>Department of Chemistry and Chemical Engineering, Inha University, </i><sup>2</sup><i>Institute of Advanced Composite Materials, KIST</i></p>   |